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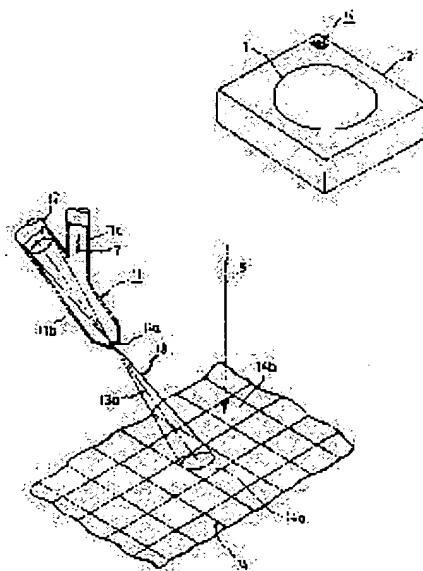
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**(54) CHARGED PARTICLE BEAM TYPE PROCESSING DEVICE****(57)Abstract:**

**PURPOSE:** To efficiently execute charged particles beam processing by using laser light and sensor to detect the deviation between an irradiation position of the charge beam and a gas blowing position and changing the direction of a gas nozzle according to the deviation quantity thereof.

**CONSTITUTION:** A gas for processing is blown from the gas nozzle 11 consisting of a body 11b having an injection part 11a and an introducing pipe 11c to the work, such as semiconductor wafer 1, imposed on a sample base 2 set to a positioning device (not shown), such as X-Y table, and the work is irradiated with the charge beam, such as electron beam 5, by which the work is subjected to processing, such as etching. The work is irradiated with the laser light 13 coaxial with the gas nozzle 11 by a laser light projecting device having a lens 12, etc., of the above-mentioned charged particle beam type processing device. This laser light 13 is detected by a two-dimensional detector 14, such as CCD. The above-mentioned electron beam 5 is then detected. The deviation in the blowing position of the gas 7 with respect to the irradiation position of the electron beam 5 is detected in this way. The direction of the nozzle 11 is changed according to this deviation quantity to determine the gas blowing position at the position to be irradiated with the electron beam.

**LEGAL STATUS**

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